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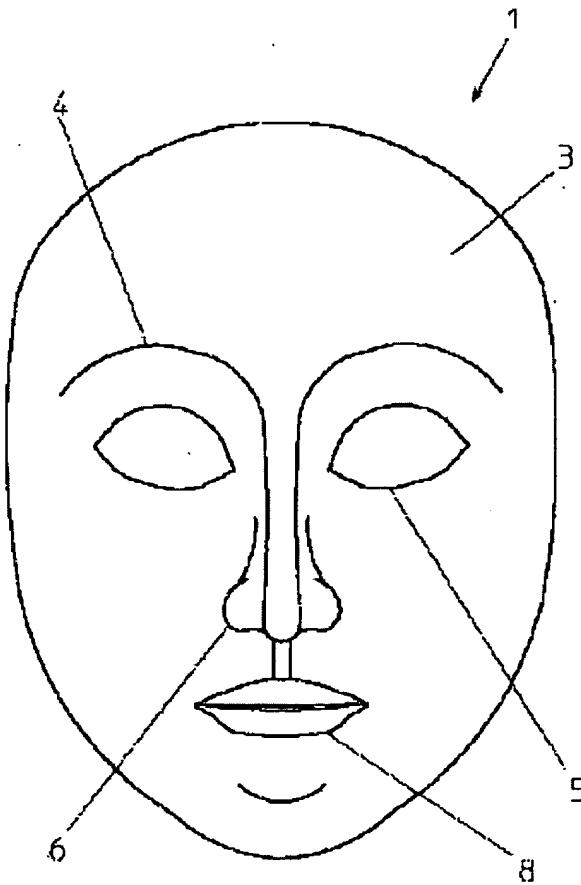
FAR INFRARED RAYS MASK

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Abstract of JP2001145520

PROBLEM TO BE SOLVED: To provide a mask which generates far infrared rays, tenders and activates the skin and can give off perfume.

SOLUTION: The inner face of a mask is made into a recessed face being approximately along the human face. Far infrared rays are generated by warming it. The mask is formed by adding a mineral or ceramic powder into a heat-resistant plastic type rubber for a mask material. The inner face of the mask is made into a face with a fine unevenness to obtain a face with water retention characteristics and a perfume is sprayed or the perfume is kneaded into a mask formable material to obtain a fragrant mask. A hygienic mask is formed by kneading an anti-fungus agent in the skin part of the inner face of the mask or the whole thickness part of the mask.



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